

Microlithography Chemical Corp.

1254 Chestnut Street Newton, MA 02164-1418 Tel: (617) 965-5511

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MATERIAL SAFETY DATA SHEET

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SECTION I. CHEMICAL IDENTIFICATION -----

CHEMICAL NAME: TRADE NAME:

Organic Solvent Mixture NANO™ Remover PG

Positive radiation Resist remover

PRODUCT #:

G050200

SECTION 2. COMPOSITION-----

INGREDIENTS:

N-Methyl Pyrrolidinone (CAS: 872-50-4); >99%

OTHER

INGREDIANTS:

Proprietary Surfactant; <1%

SECTION 3. HAZARD DATA-----

INFLAMMABILITY:

SKIN CONTACT:

EYE CONTACT:

INGESTION:

INHALATION: MUTAGENICITY:

CARCINOGENICITY:

OTHER:

TARGET ORGANS:

Combustible liquid.

Moderate skin irritation. Severe eye irritant.

May be harmful if swallowed in large quantities.

No inhalation hazard identified. Not known to be mutagenic.

Not considered carcinogenic by NTP, IARC and OSHA

Bone Marrow, Thymus.

SECTION 4. FIRST AID MEASURES-----

INHALATION:

If inhaled, remove to fresh air. If patient has stopped breathing, give

artificial respiration. If breathing is difficult give oxygen. Obtain

emergency medical attention.

INGESTION:

Wash out mouth with water if conscious. DO NOT induce

SKIN CONTACT:

Rinse with water for 15 minutes while removing contaminated clothing and shoes. Wash affected area with soap and water. Wash

contaminated clothing.

EYE CONTACT:

Rinse immediately with water, flush for 20-30 min. lifting eyelids

frequently. Get emergency medical assistance.

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SECTION 5. FIRE FIGHTING MEASURES----

EXTINGUISHING

MEDIA:

SPECIAL FIRE FIGHTING

PRECAUTIONS:

Dry chemical, carbon dioxide, foam, water spray, fog. Wear self-contained breathing apparatus (SCBA) and personal

protective equipment.

UNUSUAL FIRE OR

EXPLOSION HAZARDS:

Vapor may travel considerable distance to source of ignition and flash back. Heat will build pressure and may rupture closed containers. Keep containers cool with water spray.

SECTION 6. ACCIDENTAL RELEASE PROCEDURES ----

Evacuate Area.

Eliminate all ignition sources.

Wear self-contained breathing apparatus (SCBA), rubber boots, and heavy rubber gloves. Avoid eye or skin contact. Cover with dry absorbent material and collect in closed container for disposal using non-sparking tools. Ventilate area and wash spill site after material pickup is complete, rinse with water. All clean-up should be carried out in accordance with federal, state, and local regulations. If required proper authorities should be notified.

SECTION 7. STORAGE AND HANDLING PRECAUTIONS-----

STORAGE:

Store in tightly closed container in a cool environment away from

direct sunlight.

HANDLING:

Keep away from heat, sparks, and flames.

Do not breathe vapors. Possible teratogen.

Use only with mechanical exhaust.

Do not contact with skin, eyes, and clothing. Avoid prolonged or repeated exposure.

Wear heavy rubber gloves.

Wash with soap and water after handling. Have safety shower and eye wash available.

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SECTION 8. EXPOSURE CONTROLS AND PERSONAL PROTECTION-----

RESPIRATORY

PROTECTION:

In case of spills, use of self-contained breathing apparatus (SCBA)

is recommended.

VENTILATION:

Local or general mechanical ventilation is required.

SKIN PROTECTION: EYE PROTECTION: Rubber gloves are highly recommended. Safety goggles are highly recommended.

SECTION 9. PHYSICAL AND CHEMICAL DATA-----

APPEARANCE:

Colorless Liquid.

ODOR:

Amine like. 202 °C (396 °F)

BOILING POINT:

1.026

SPECIFIC GRAVITY: VAPOR PRESSURE:

0.3 mm @ 20 °C (68 °F)

H2O SOLUBILITY:

complete

% VOLATILES:

100% by weight

EVAPORATION RATE:

0.06 (BuAc=1)

FLASH POINT: AUTOIGNITION TEMP: 93 °C (199 °F) TCC 270 °C (518 °F)

EXPLOSION LIMITS:

1.3 lower

9.5 upper

STABILITY:

Stable

INCOMPATIBILITY:

Strong Oxidizing Agents, Strong Acids

HAZARDOUS POLYMERIZATION:

SECTION 10. REACTIVITY DATA -----

Will not occur

HAZARDOUS COMBUSTION OR DECOMPOSITION PRODUCTS:

Carbon Monoxide, Carbon Dioxide, Nitrogen Oxides.

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SECTION 11. TOXICITY HAZARDS-----

ACCUTE EFFECTS:

May be harmful if swallowed, inhaled, or absorbed through the skin.

Irritating to the eyes and respiratory tract. May cause sever irritation to the eyes. Vapor or mist is irritating to the eyes, mucous membranes and upper respiratory tract. Prolonged exposure can cause stomach pains, nausea, vomiting, and/or diarrhea. Overexposure may cause reproductive disorders affecting pregnancy and/or fetal development

ORAL:

LD50(rat):

3914 mg/kg

IRRITATION:

Eyes:

100 mg moderate

TLV:

ACGIH(TWA)

none established

PEL:

OSHA (8 hr TWA)

none established

SECTION 12. ECOLOGICAL DATA-----

No data available at this time.

SECTION 13. DISPOSAL CONSIDERATIONS-----

Burn in an EPA-licensed chemical incinerator equipped with an afterburner and scrubber at an approved waste disposal facility. Observe all federal, state, and local environmental regulations.

SECTION 14. TRANSPORTATION INFORMATION-----

HAZARD CLASSIFICATION:

Combustible Liquid

SHIPPING NAME:

Flammable Liquid, NOS (n-methylpyrrolidinone)

UN NUMBER:

NA 1993

PACKING GROUP

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SECTION 15. REGULATORY INFORMATION-----

HAZARDOUS LISTINGS:

All ingredients appear on the TSCA Inventory of Chemical Substances, EINECS, and the Japan

Hazardous Chemical Listing.

SARA Title III:

This product IS NOT subject to SARA Title III, Section

313 Reporting Requirements.

Calif. SCAQMD Rule 443.1 VOC's: 1026 g/l; vapor pressure 0.3 mm Hg @ 20 °C

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SECTION 16. ADDITIONAL PRECAUTIONS AND COMMENTS-----

To the best of our knowledge, the above information is believed to be accurate but does not claim to be all inclusive and is intended to be used only as a guide. The supplier makes no warranty of any kind, expressed or implied, concerning the use of this product and shall not be held liable for any damage resulting from handling or from contact with the above product. User assumes all risks incident to its use.

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50-8 stripper



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NANO REMOVER PG

POSITIVE RADIATION SENSITIVE RESIST REMOVER

Product No. Expiration G050200 May-98 Lot No. Manufactured 97013 Apr-97

CERTIFICATE OF ANALYSIS

MICROLITHOGRAPHY CHEMICAL CORP. has completed the analysis of the above lot of material with the results listed below.

Appearance Clear, colorless

Solvent by GC >99% N-Methylpyrrolid-inone

Evaporation Residue <0.01%

Filtration Level 0.1 μm

Certified by:

3-Apr-97

Vincent Urdi Chemist